## PPLEMENTAL INFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE PROSECUTION OF THE SUBJECT APPLICATION

Applicants:

F.M. Schellenberg et al.

Attorney Docket No.: MEGC122529

Application No.: 10/811,418

Art Unit: 2825 / Confirmation No.: 2647

Filed:

March 26, 2004

Examiner: Binh C. Tat

Title:

CREATING PHOTOLITHOGRAPHIC MASKS

## **U.S. PATENT DOCUMENTS**

*Examine		Decument No	Kind	Date	Nama	
Initials_	No.	Document No.	Code	(mm/dd/yyyy)	Name	
120	U16	6,416,907	<b>B</b> 1	07/09/2002	Winder et al.	
125	_ U17	6,620,561	· B2	09/16/2003	Winder et al.	

## FOREIGN PATENT DOCUMENTS

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*Examiner Cite			Kınd	Publication Date		Abstract	Translation
Initial 1	No.	Document No.	Code	(mm/dd/yyyy)	Country	Provided	Provided

None

## OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner	Cite		
Initial	No.		

None

Examiner

**Date Considered** 

\*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

RCT:jh